

On possible development of MAPS (monolithic active pixel sensor) based on spherical p-n junction

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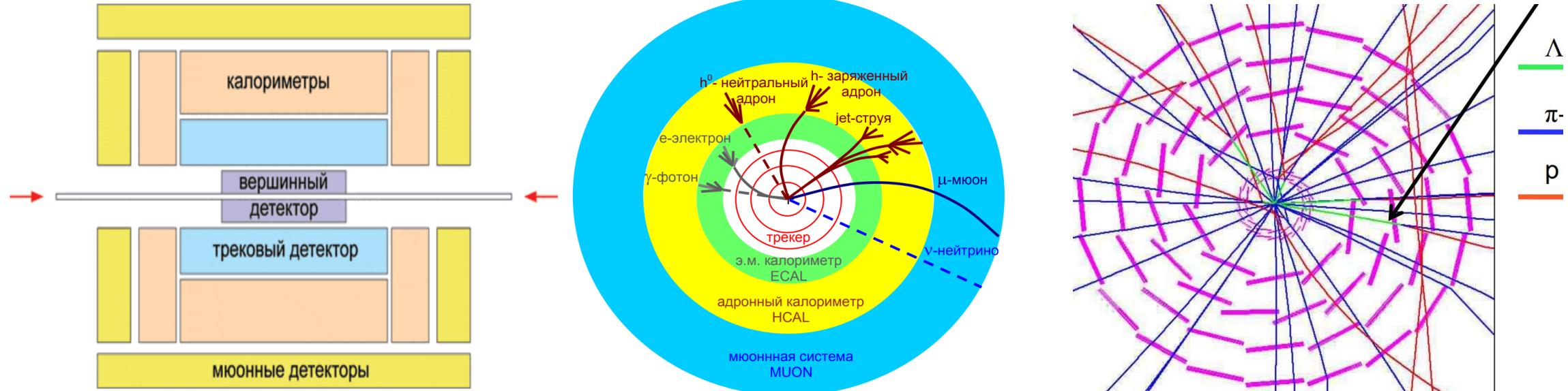
*Solid State Physics Division, P.N. Lebedev Physical Institute
Silicon Photomultiplier Lab, NRNU MEPhI
CERN CMS collaboration*

Outline

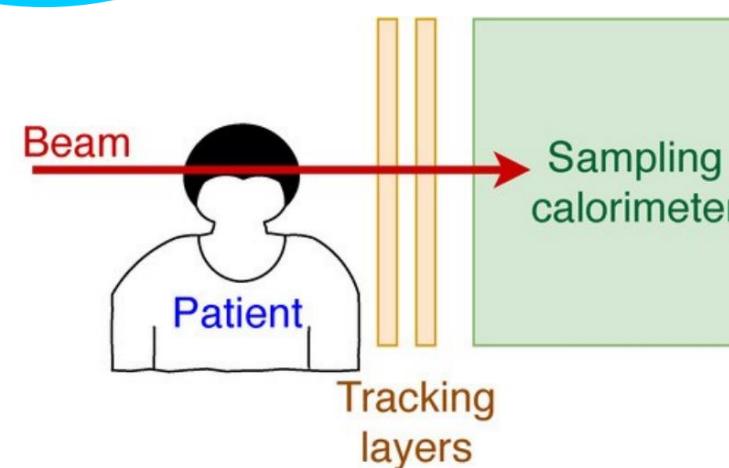
- Demands for sensors produced in Russia
- Designs of MAPS (monolithic active pixel sensor)
- Development of Tip APD – Silicon Photomultiplier based on spherical p-n junction
- On possible development of MAPS

Pixel sensors for vertex / tracking detectors

- High demands in particle detectors

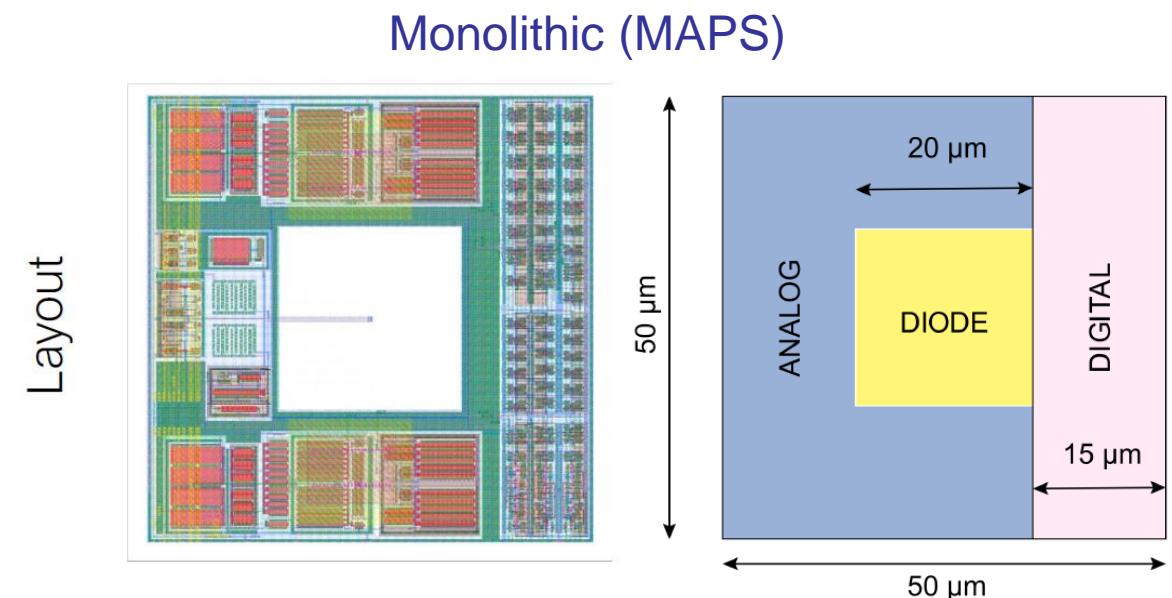
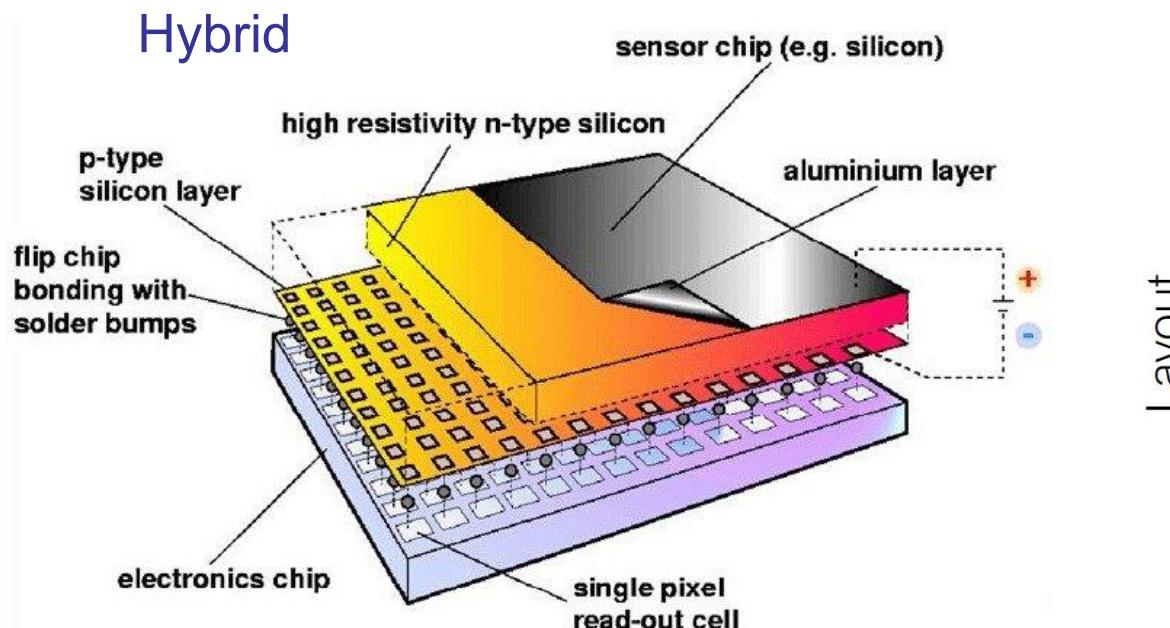


- High demands in nuclear medicine



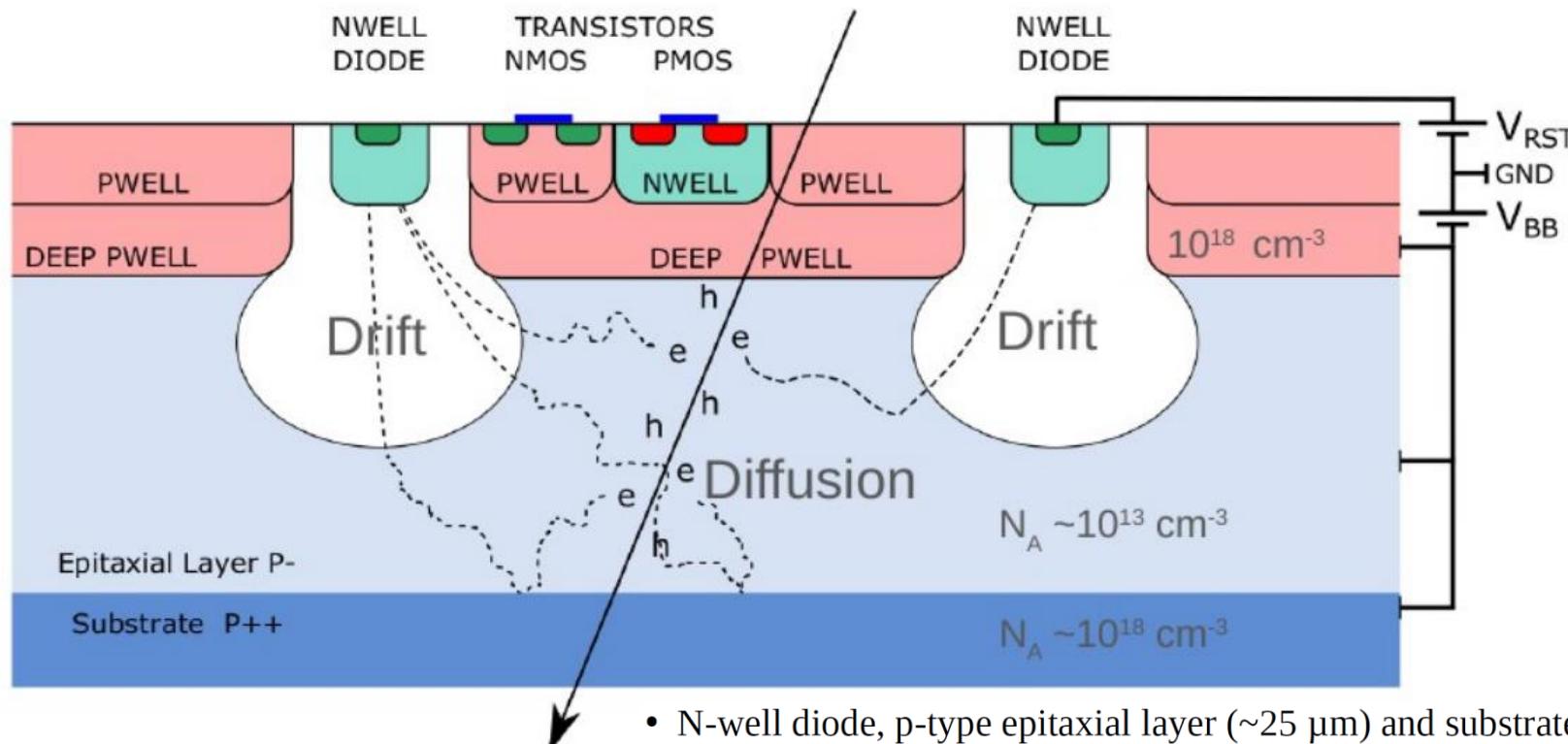
Monolithic vs Hybrid

- Hybrid = sensor chip + FEE chip coupled by flip-chip integration
 - ◆ Became obsolete, large total thickness => particle scattering and resolution losses
- Monolithic = sensor region + FEE region on the same Si wafer
 - ◆ Many advantages, intense R&D at high-tech centers, reproduction started in China



MAPS-ALPIDE – partial depletion design

- Partial depletion => slow charge collection, low radiation hardness

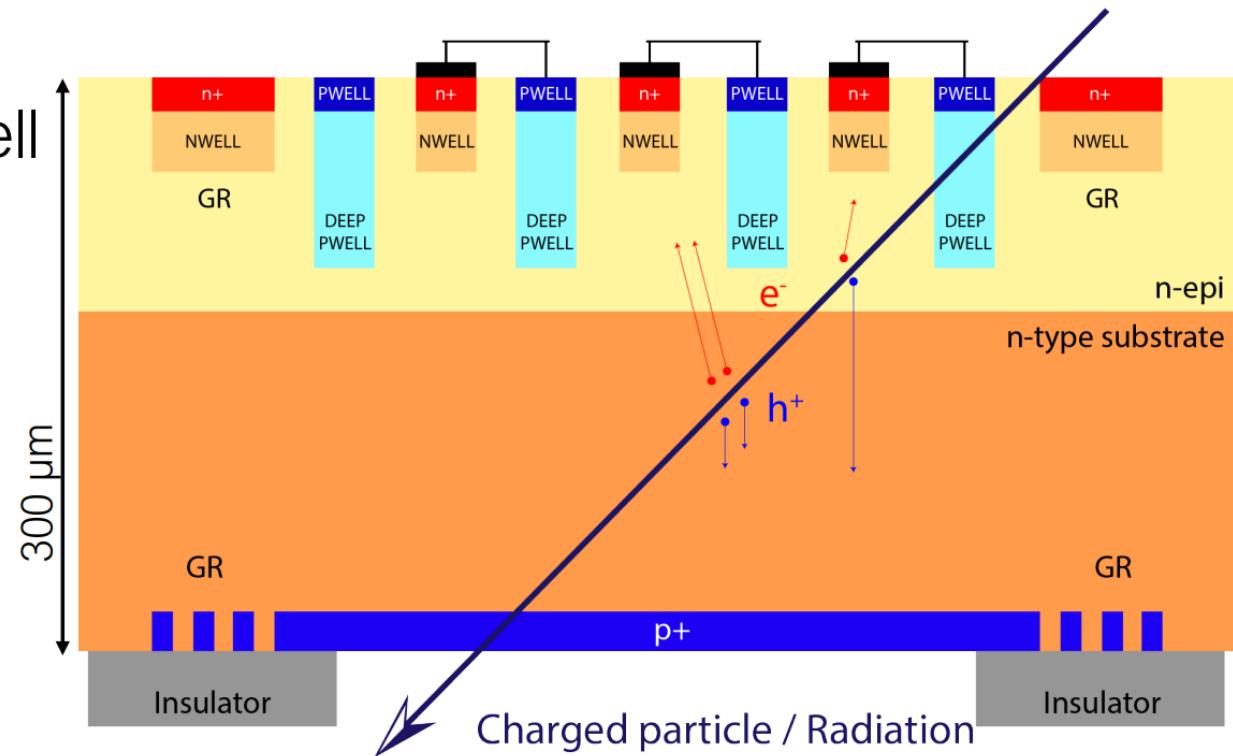


- N-well diode, p-type epitaxial layer ($\sim 25 \mu\text{m}$) and substrate
- Diode size ($2-3 \mu\text{m}$) – very small than pixel size – low capacitance – high S/N
- Possible to reverse bias (up to -6 V)
- Drift e- reaching the collection diode **induce a current signal at the input of transistors**
- Deep PWELL shields NWELL of PMOS transistors
 - allows full CMOS circuitry in active area

FD-MAPS (ARCADIA) – full depletion design

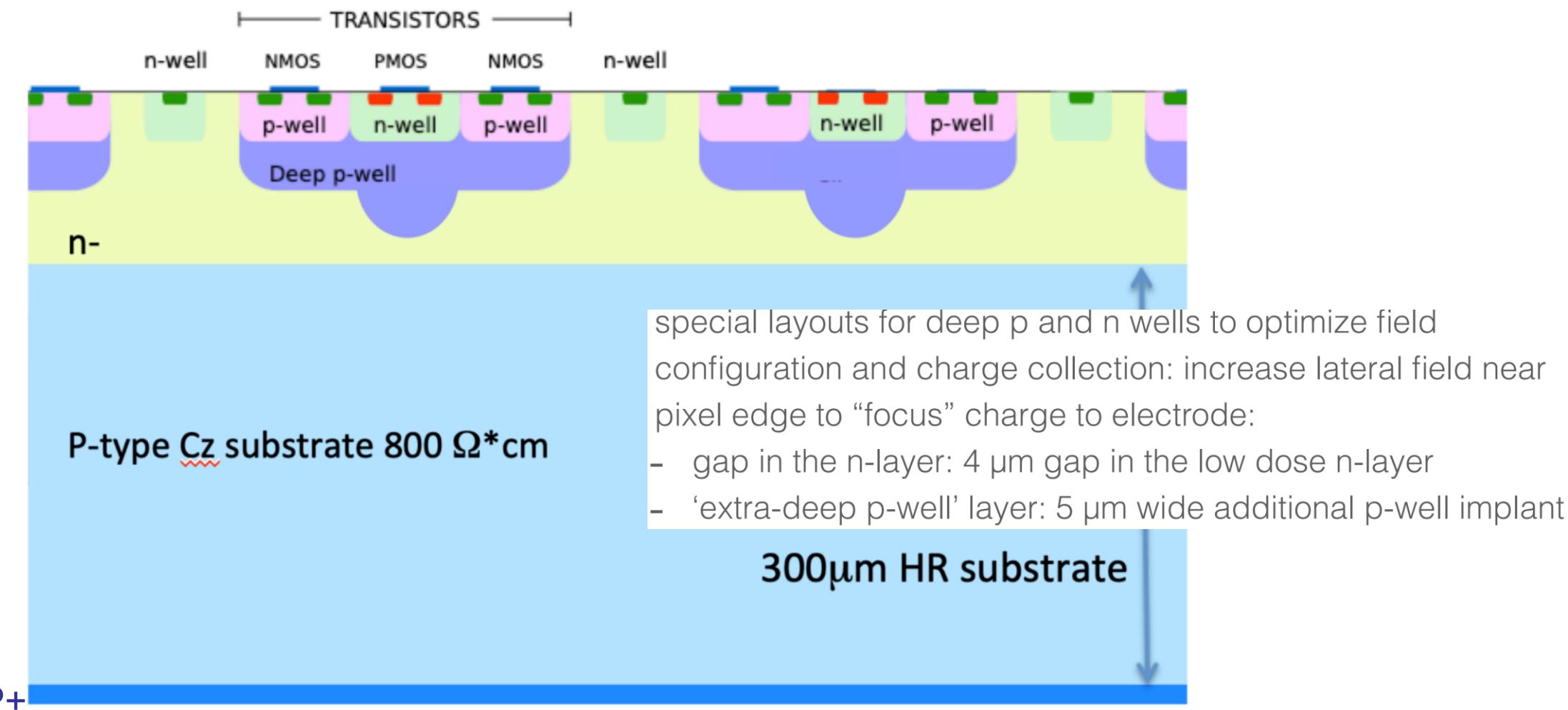
- Full depletion at -160 V @300 um Si, -40 V@100 um Si sensor thikness

- Standard CMOS process
 - Electronics buried in deep p-well
 - n-type high ρ substrate
 - Back-side standard CMOS process
 - Fully depleted substrate
-
- Drift charge collection
 - Bulk rad hardness



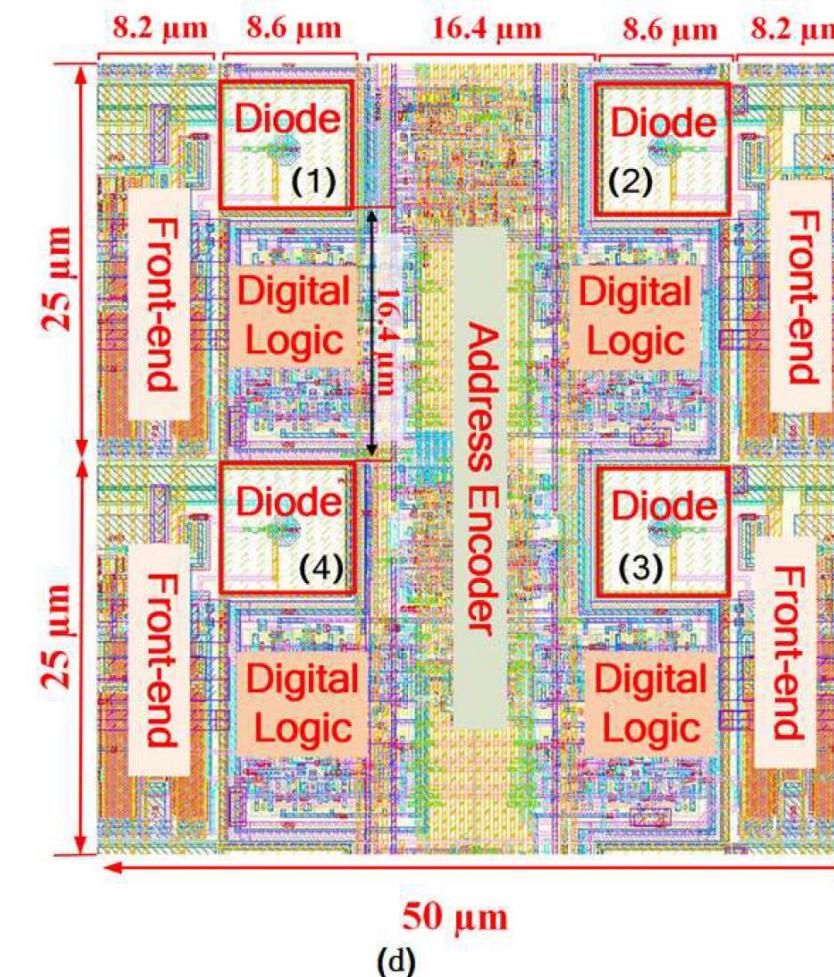
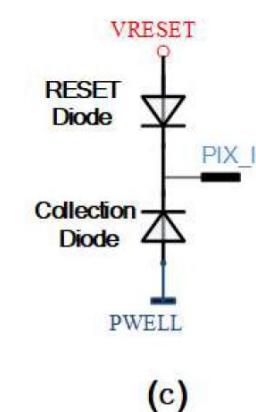
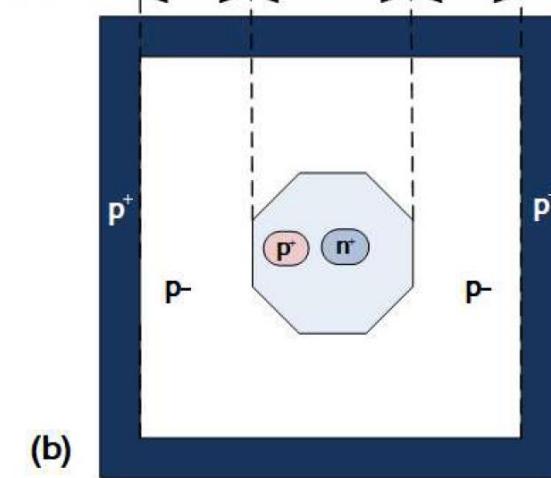
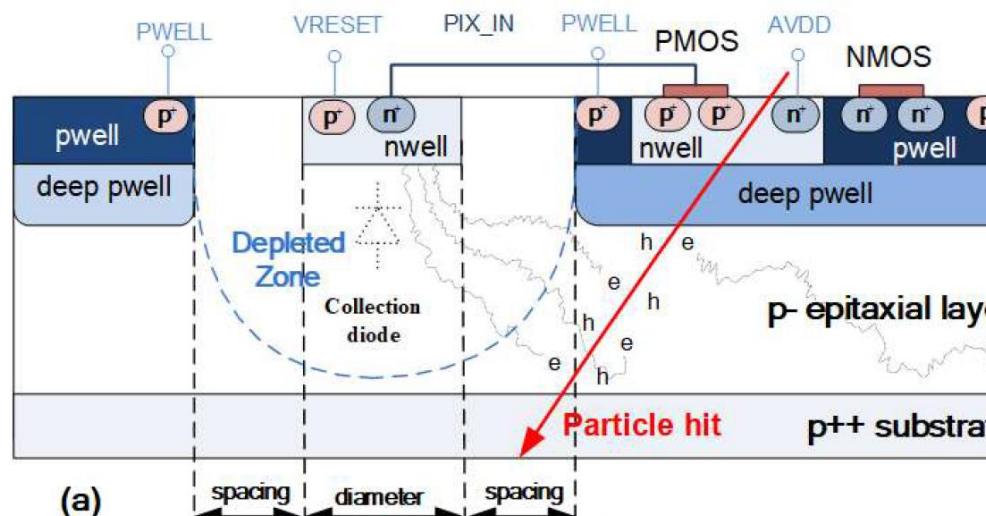
MALTA – full depletion + charge focusing

- Prototype: 100 μm thick, 36 μm pixel, full depletion at -6 V, operating voltage \leq -50 V

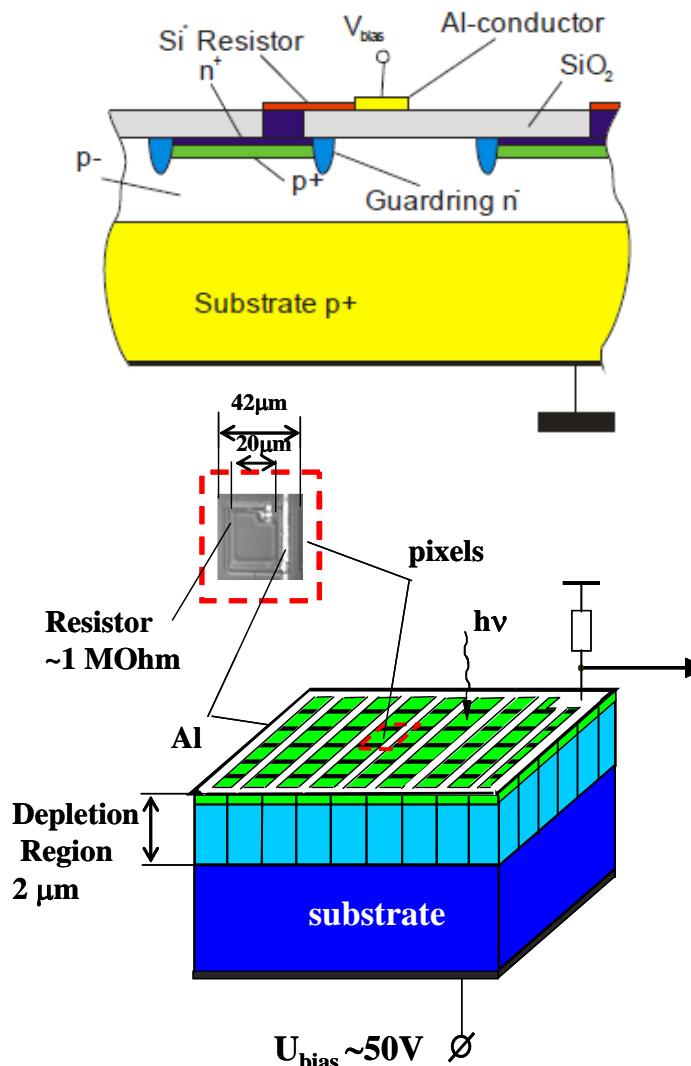


Reproduced in China: TaichuPix1 \approx MAPS-ALPIDE

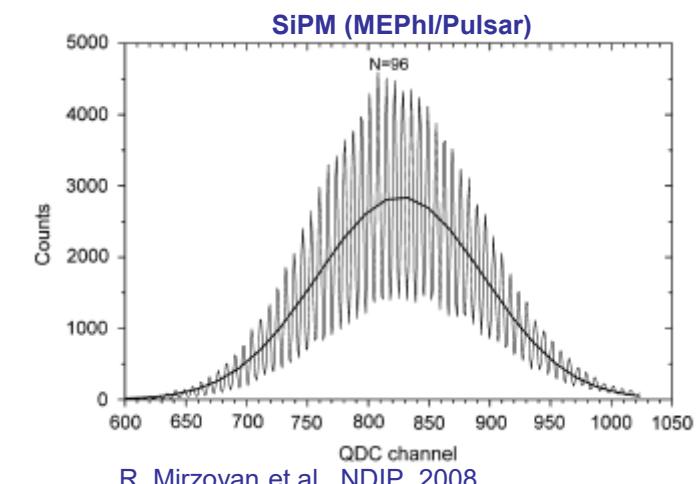
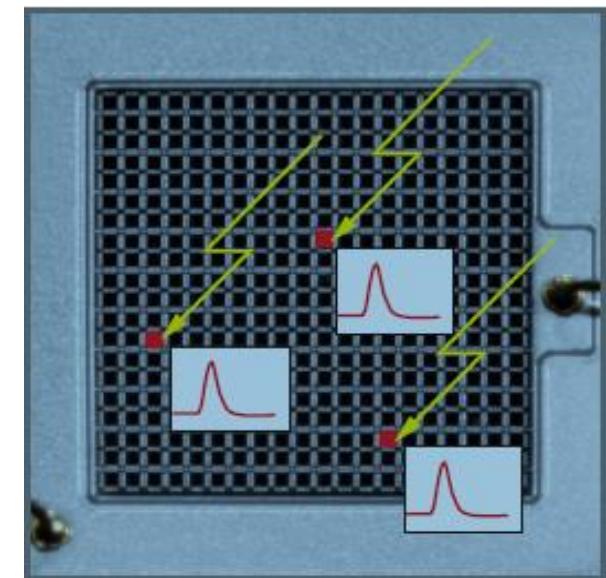
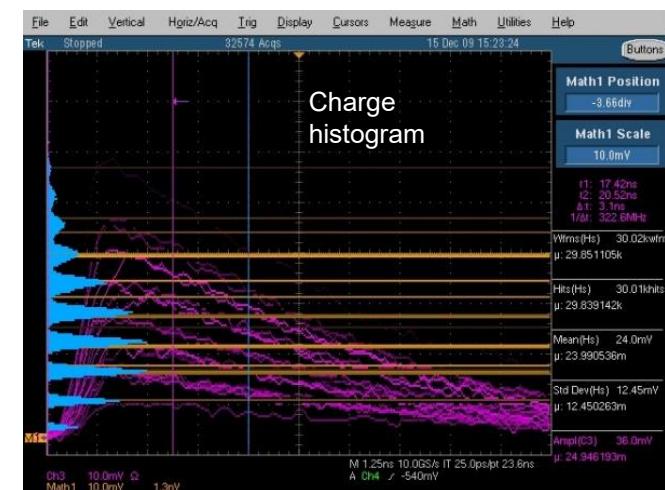
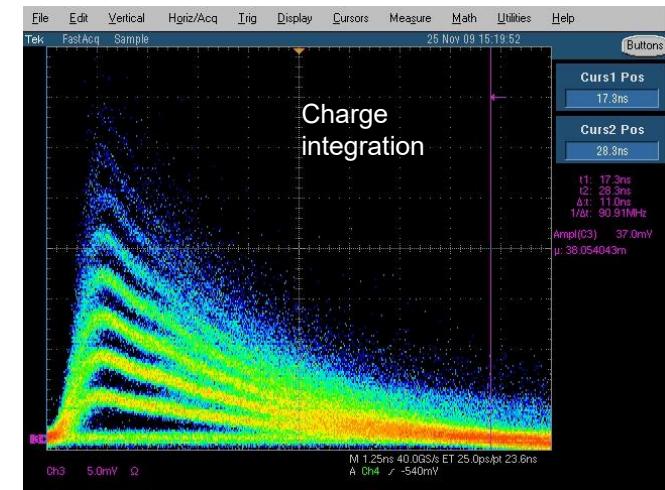
- Prototype 2022: Si-epi 25 um, pixel size 25 um, array 192×64 ($\sim 512 \times 1024$ to be in 2023)



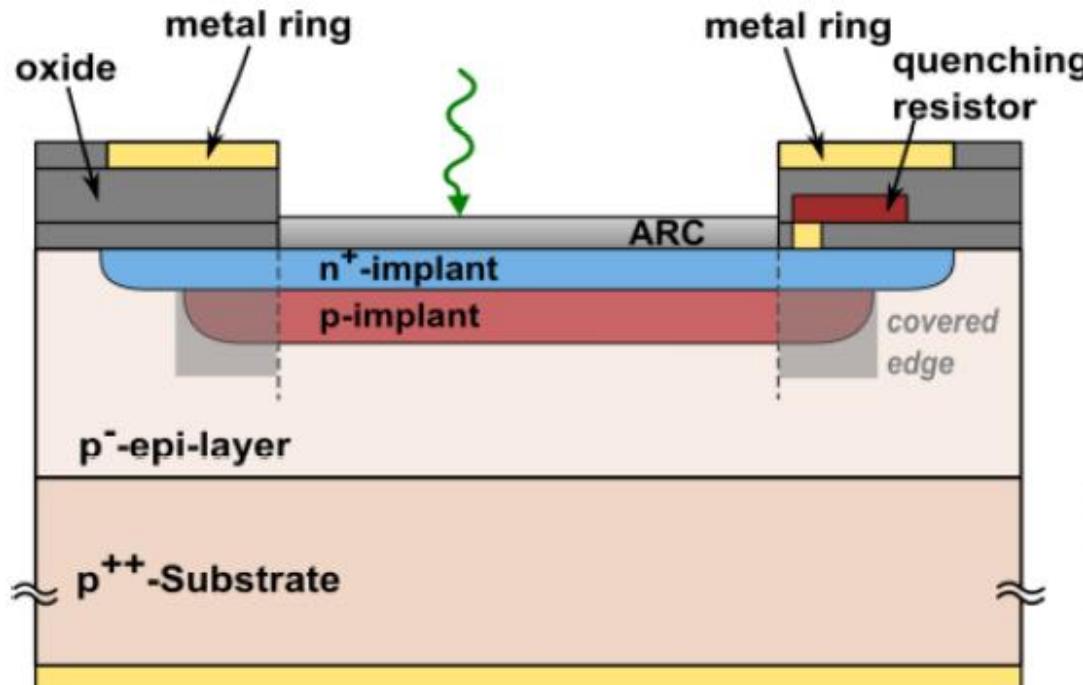
R&D on Silicon Photomultiplier (SiPM): basic studies (1980s, LPI), MRS APD (1990s, CPTA), SiPM (2000s, MEPhI)



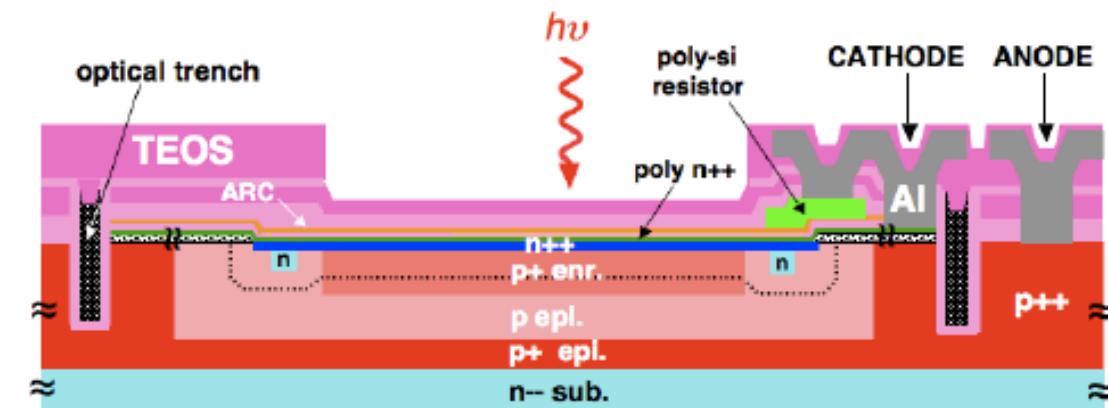
P. Buzhan, B. Dolgoshein et al, ICFA Instrum. Bull., 2001



Modern SiPMs based on planar p-n junction (MEPhI design): Hamamatsu, ST Microelectronics, Excelitas, SensL/On Semiconductor, FBK/Broadcom

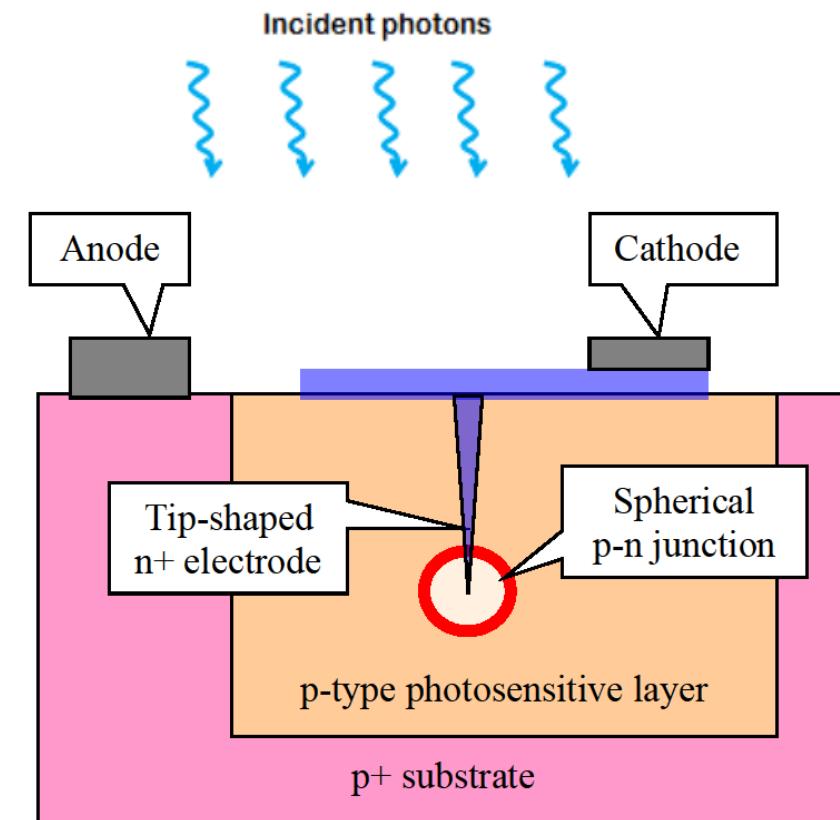
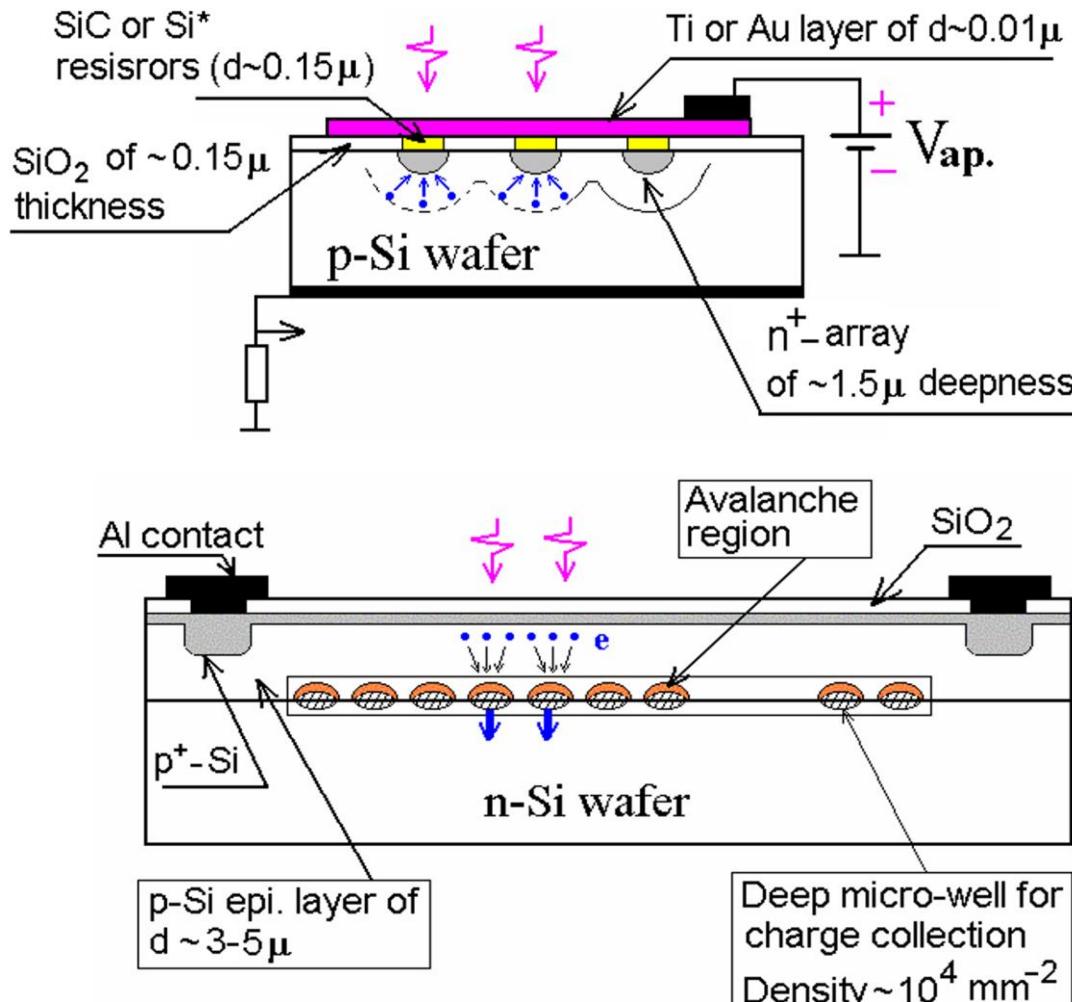


FBK



ST Microelectronics

Non-planar SiPM designs based on quasi-spherical p-n junctions: Metal-Resistor-Semiconductor APD, Micro-well APD, Tip APD



Sadygov, Z. Three Advanced Designs of Avalanche Micro-Pixel Photodiodes (NDIP 2005)

Vinogradov, S. Tip Avalanche Photodiode—A Spherical-Junction SiPM Concept (NIMA 2023)

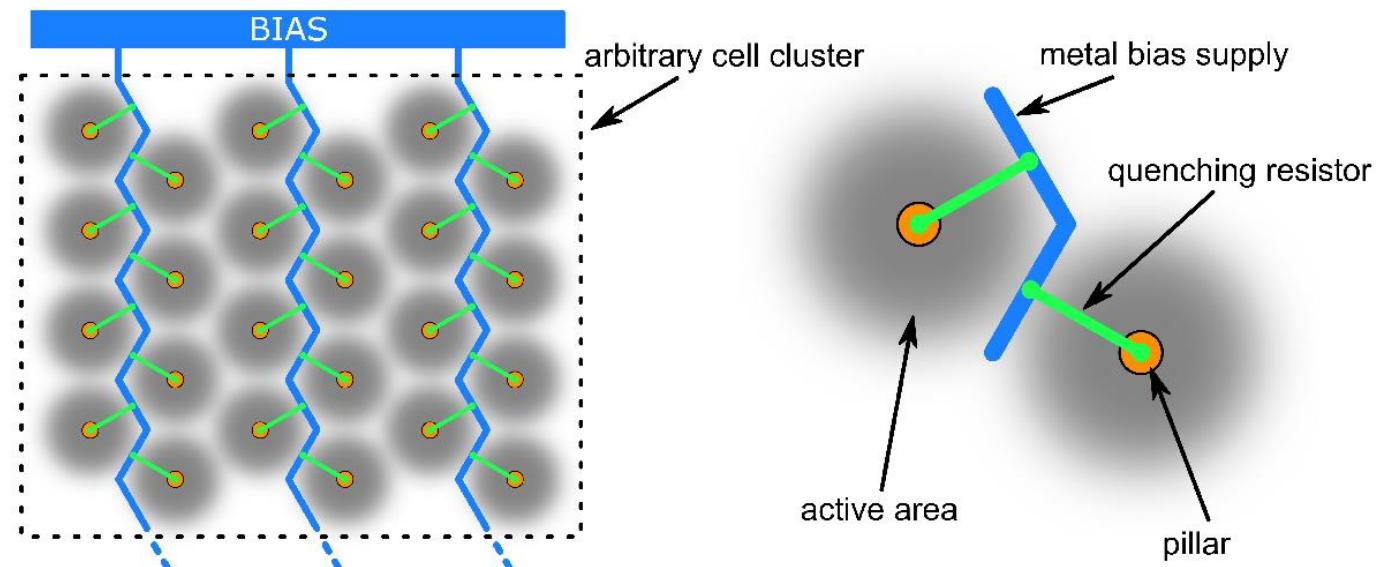
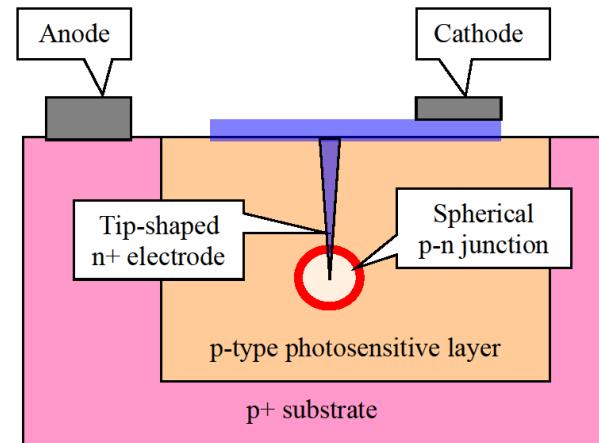
Advantages and drawbacks of TAPD

○ Advantages

- ◆ High efficiency (no cell boundaries) => high PDE;
- ◆ Low capacitance =>
 - fast timing response, fast recovery $\sim RC$,
 - low readout noise $\sim kTC$;
- ◆ High Dynamic Range (small cells)
- ◆ Low breakdown voltage =>
 - low power consumption,
- ◆ Low size of high electric field region =>
 - low DCR by SHR (TBD)
 - radiation hardness (TBD);

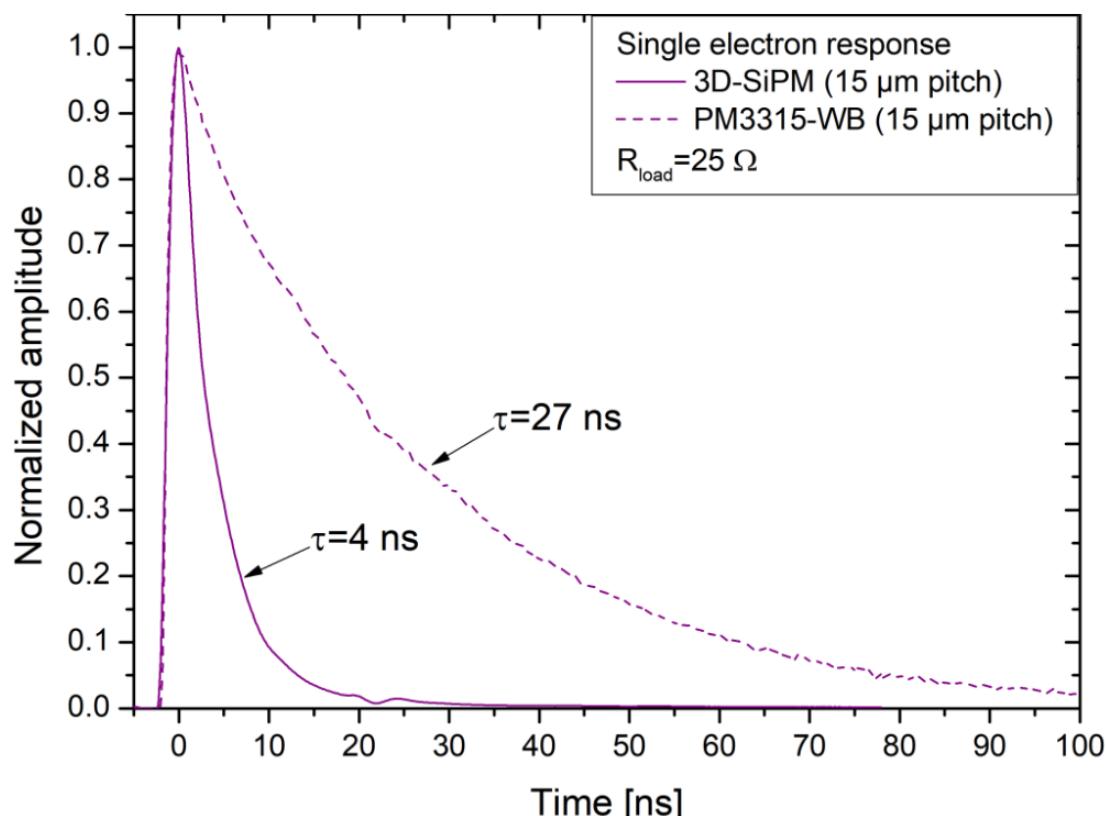
○ Drawbacks

- ◆ High sensitivity of V_{bd} to the tip radius
- ◆ High risk of tunneling near the tip
- ◆ Questionable reproducibility of the tips

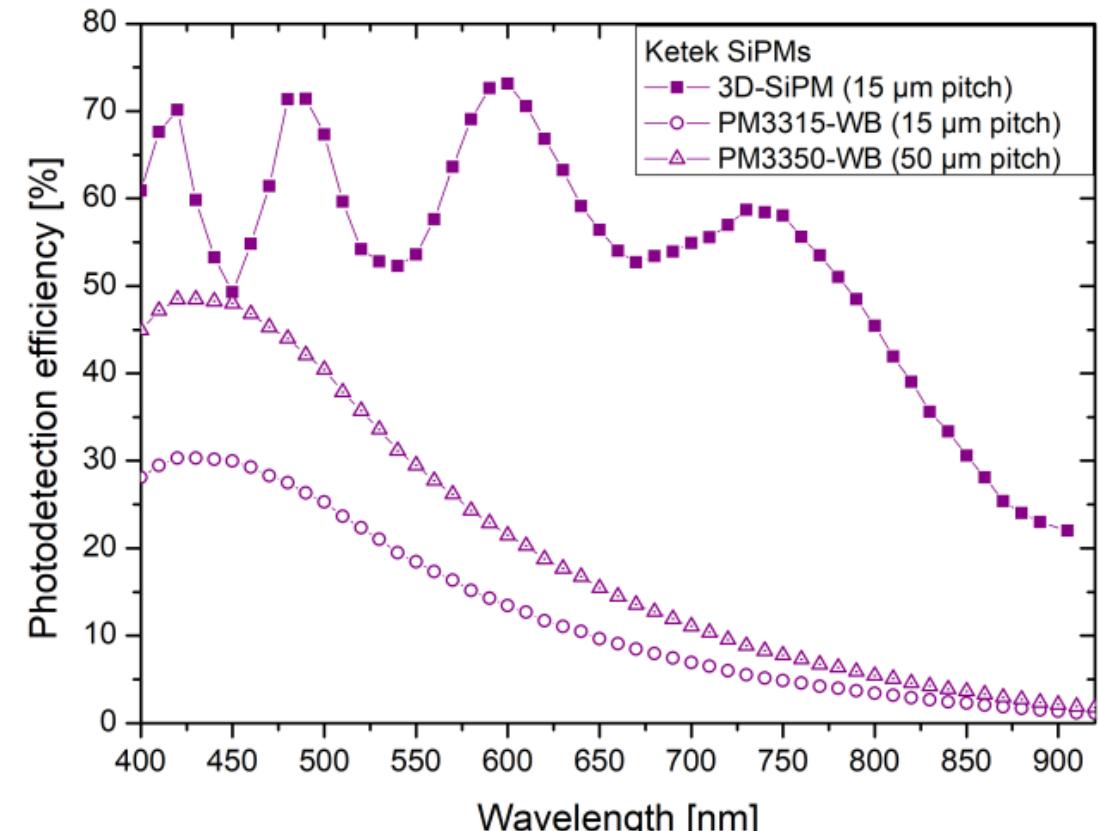


TAPD developed in collaboration with KETEK (2017 – 2020): record performance

- Single electron response time = **4 ns**
- Single cell recovery time = **4 ns**



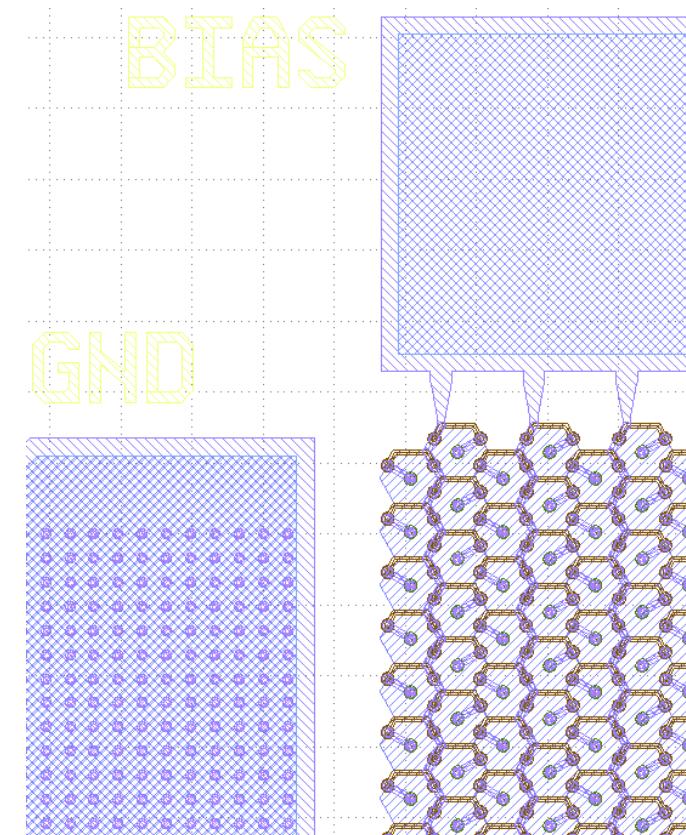
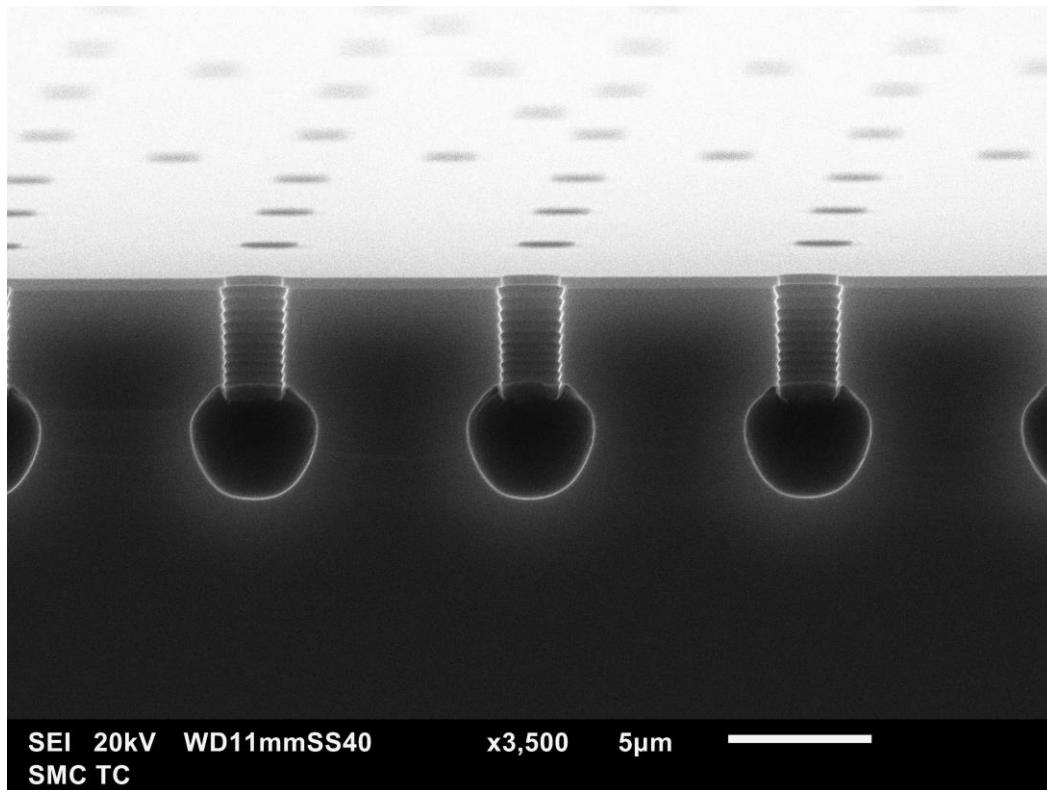
- Max PDE = **73%** (608 nm)
- NIR PDE = **22%** (905 nm)
- Wide spectral range: PDE $\geq 50\%$ (400 – 800 nm)



Engelmann, E.; Schmailzl, W.; Iskra, P.; Wiest, F.; Popova, E.; Vinogradov, S. Tip Avalanche Photodiode—A New Generation Silicon Photomultiplier Based on Non-Planar Technology. *IEEE Sens. J.* **2021**, *21*, 6024–6034, doi:10.1109/JSEN.2020.3041556.

Проект по разработке SiPM непланарной конструкции с МИЭТ

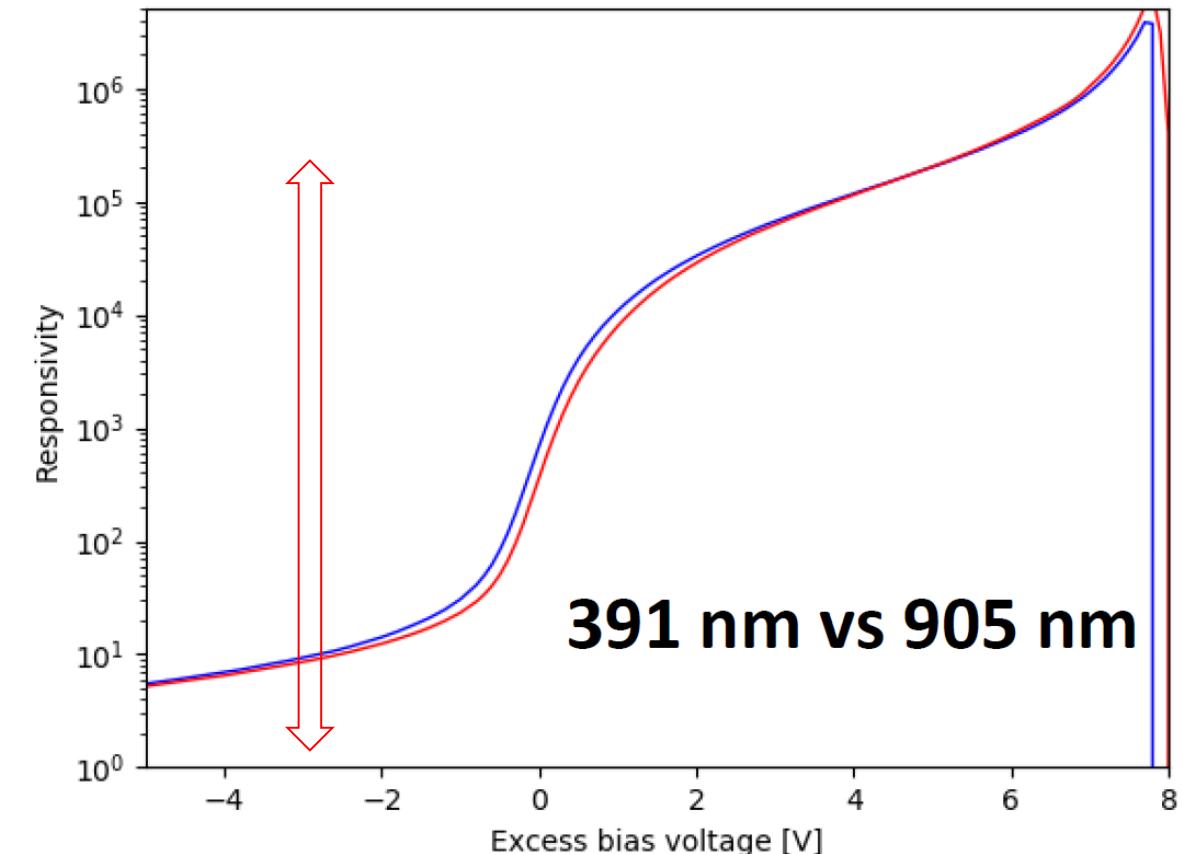
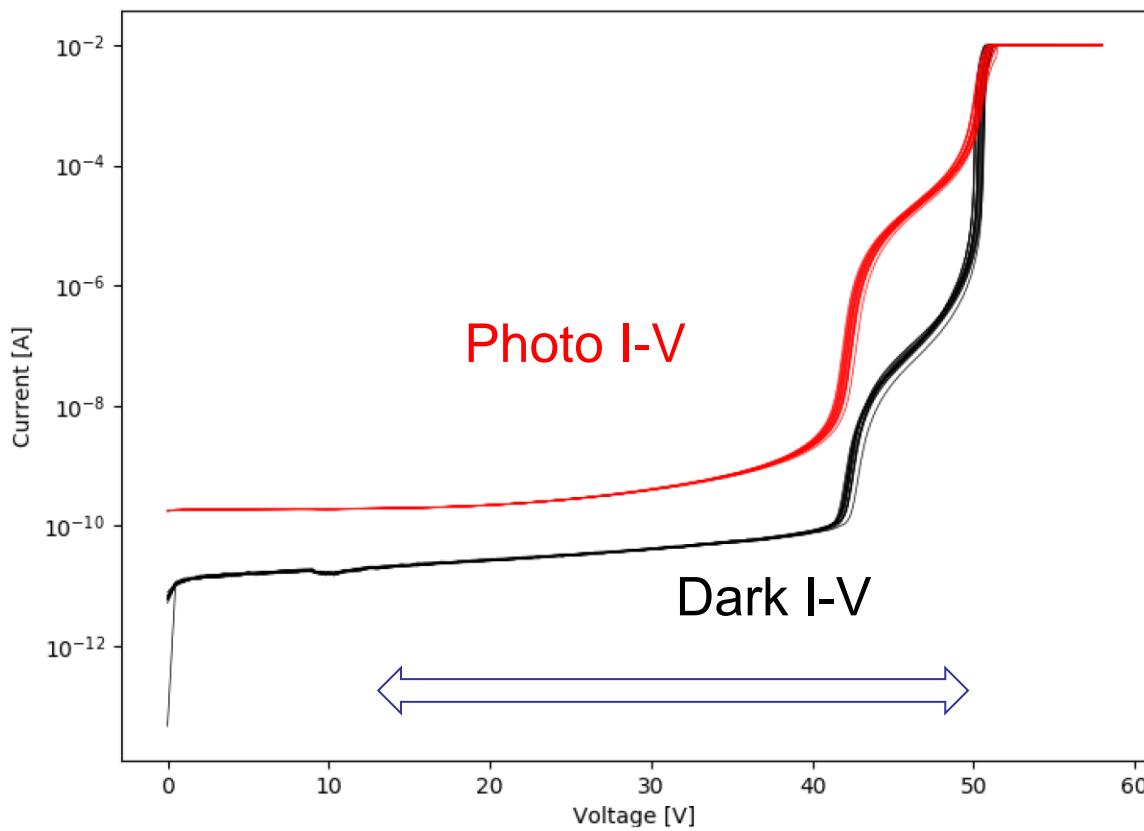
- Ведется НИОКР «Разработка нового типа кремниевых фотоумножителей непланарной конструкции»
 - ◆ Грант фонда содействия инновациям «Техностарт-1» на 2022 – 2023 гг.
 - ◆ На технологической базе ЦКП и ТЦ МИЭТ, гл. технолог А.А. Жуков
 - ◆ Разработаны ключевые элементы технологии, техпроцесс, фотошаблоны
 - ◆ Выпуск 1-й партии планируется летом 2023



Адаптивный коэффициент умножения: $10 \dots 10^6$ @ $\Delta U = 10$ V

Gain ~ 10 @ $U \sim 40$ V, $I_{\text{dark}} \sim 40$ pA/mm 2

Gain $\sim 10^6$ @ $U \sim 50$ V, $I_{\text{dark}} \sim 0.5$ mA/mm 2



Заключение

- Возможные конструкции непланарных SiPM + MAPS:
 - ◆ SiPM + MAPS-ALPIDE
 - ◆ SiPM + FD-MAPS
- Возможные преимущества конструкций:
 - ◆ Сенсор и активная электроника изолированы и независимы
 - ◆ Сенсор имеет минимальную ёмкость (сфера) и адаптивную чувствительность (лавина)
 - упрощение электроники (без усиления)
 - уменьшение толщины сенсора (меньше рассеяние)
- Возможность разработки и выпуска в Зеленограде - рассматривается
 - ◆ Сергей Викторович Змеев, МИЭТ
- Возможность заинтересованности BM@N – предполагается
 - ◆ Михаил Моисеевич Меркин, НИЯФ МГУ



Российской академии наук



СПАСИБО ЗА ВНИМАНИЕ!

Вопросы?
Замечания?
Предложения?

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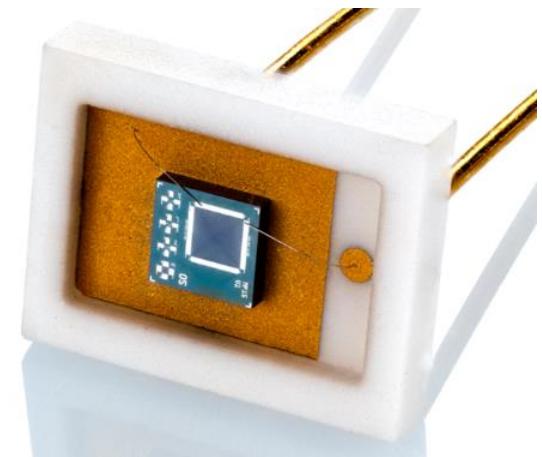
Разработка TAPD SiPM

- НИОКР в сотрудничестве с компанией KETEK, Германия (2017-2020)
 - ◆ На технологической базе KETEK, X-Fab, Fraunhofer EMFT
- Образцы TAPD 1x1 мм², шаг ячеек 10 – 15 мкм, радиус 0.6 – 1 мкм

Structure Name	Nominal Radius (r_j)	Breakdown Voltage
S06	0.6 μm	43.4 V
S08	0.8 μm	50.7 V
S10	1.0 μm	53.9 V

- Измерения образцов в KETEK и МИФИ
 - ◆ Подтверждение рекордных параметров в лаборатории SiPM компании Broadcom
- Публикации (2020 - 2022)

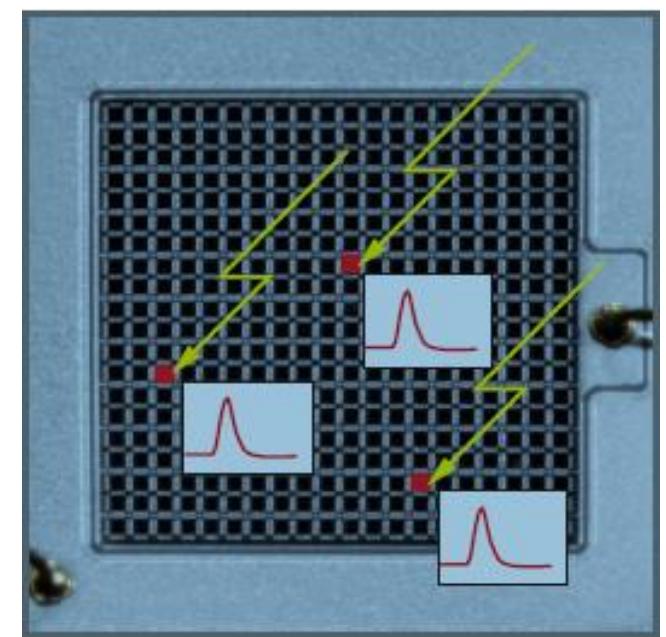
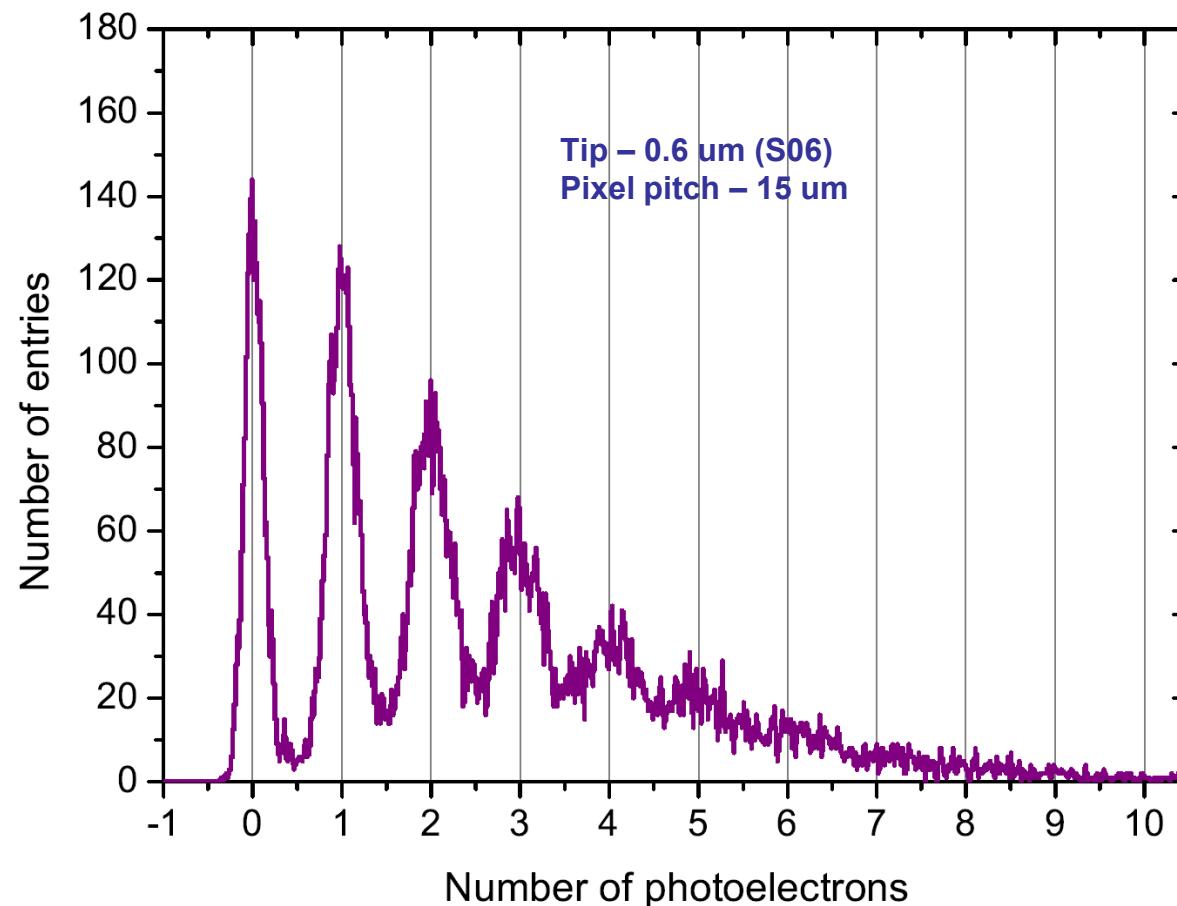
- [1] E. Engelmann, W. Schmailzl, P. Iskra, F. Wiest, E. Popova, S. Vinogradov, “Tip Avalanche Photodiode - a new generation Silicon Photomultiplier based on non-planar technology”, *IEEE Sensors J.* (2020) Vol 21, No 5, 6024-6034
- [2] S. Vinogradov, E. Popova, W. Schmailzl, E. Engelmann “Tip Avalanche Photodiode – a new wide spectral range Silicon Photomultiplier”, “*Radiation Detection Systems*”, Taylor & Francis (2021) Vol. 1, Ch. 9, 257–288
- [3] S. Vinogradov, “Tip Avalanche Photodiode – a spherical-junction SiPM concept”, *9th Int. Conf. New Developments in Photodetection*, Troyes, France, 4 - 8 Jul. 2022.



Результаты измерений ТАРД: разрешение числа фотоэлектронов

Функциональность SiPM – разрешение числа фотонов - подтверждена

- ◆ Возможно, есть разброс радиуса сферических p-n переходов
- ◆ Характеризация по пикам по стандартным методикам SiPM



Подтверждение радиационной стойкости TAPD (2022)

- Исследования UHH/DESY Detector Lab
- Облучение тепловыми нейтронами 1 МэВ
- Дозы до 10^{12} см^{-2}
- Сравнение с планарными SiPM
 - ◆ КЕТЕК MP15: 15 мкм ячейки, $1 \times 1 \text{ мм}^2$
 - ◆ Типичная для SiPM рад. стойкость
- Рост темнового счета (при $\Phi=10^{12} \text{ см}^{-2}$)
 - ◆ TAPD – **10³ раз**
 - ◆ KETEK MP15 – 10⁵ раз

J. Römer, E. Garutti, W. Schmailzl, J. Schwandt, S. Martens,
“Radiation Hardness of a Wide Spectral Range SiPM with
Quasi-Spherical Junction”, NDIP (2022) / NIMA (2023).
<http://arxiv.org/abs/2209.07785>.

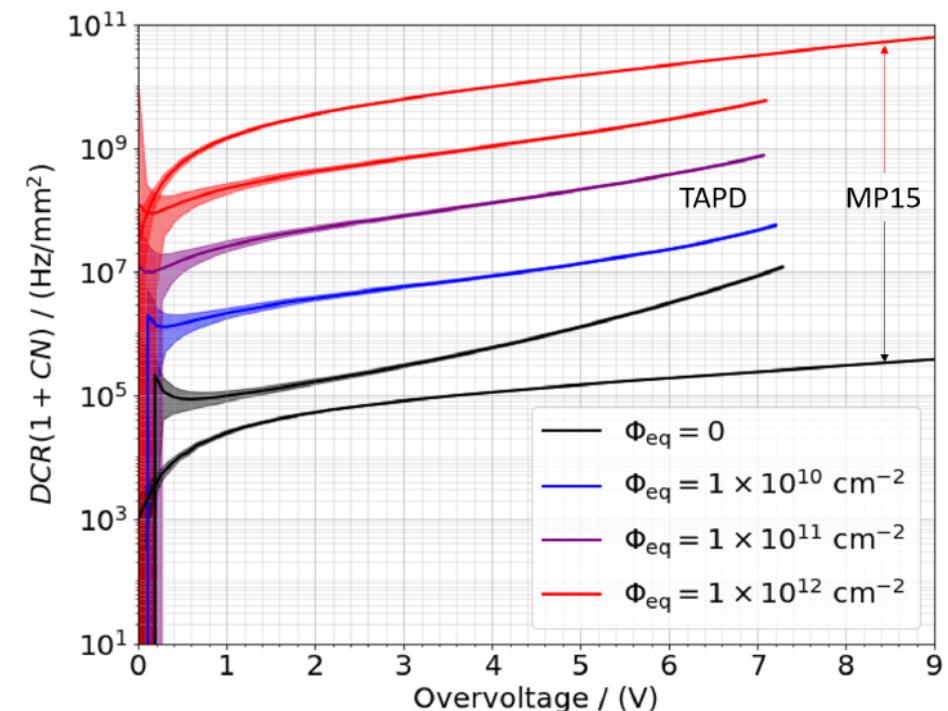


Figure 7: The dark count rate at 20 °C calculated using Eq. 7 normalized to a detector area of 1 mm² for the TAPD 0.6 μm and the MP15. The overvoltage is given as $V_{over} = V_{bias} - V_{BD}$.